Application No.	Applicant(s)
0/659,421	STRACHAN ET AL.
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Stanetta D. Isaac	2812
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's Patent Drawing Review	v ( PTO-948) attached
	ne drawings in the front (not the back) of R 1.121(d).
of BIOLOGICAL MATE OR THE DEPOSIT OF BIO	ERIAL must be submitted. Note the DLOGICAL MATERIAL.
5. ☐ Notice of In	formal Patent Application
6. 🗌 Interview Si	ummary (PTO-413),
	Amendment/Comment
8. 🛭 Examiner's	Statement of Reasons for Allowance
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	or REMAINS) CLOSED in the other appropriate community. This application is and MPEP 1308.  10/02/06.  er 35 U.S.C. § 119(a)-(d) deen received. een received in Application ments have been received.  This application.  ed. Note the attached EXA reason(s) why the oath of the submitted.  The Section of BIOLOGICAL MATE O

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## **REASONS FOR ALLOWANCE**

The following is an examiner's statement of reasons for allowance:

The closest prior art of record, Bol et al., US Patent 6,699,775 alone or in combination with of Pfirch US Patent 5,736,445, fails to show the following steps of:

Pertaining to independent claim 7, "...the perimeter surface region being defined around the perimeter of the first surface region and spaced-apart from the first surface region by a distance that is less than two times (2x) the lateral diffusion length of the dopant from the primary dopant junction during a thermal diffusion step applied to the semiconductor substrate;"

Pertaining to independent claim 8, "...a second mask opening that defines a perimeter upper surface area by a distance that is less than two times (2x) the lateral diffusion length of a dopant having a second conductivity type that is opposite the first conductivity type in the semiconductor substrate during a thermal diffusion step applied to the semiconductor substrate, the second opening having the minimum geometry feature size;"

Pertaining to independent claim 9, "...the islands areas being disposed around and spaced-apart from the perimeter of the first upper surface are by a distance that is less than two times (2x) the lateral diffusion length of a dopant in the semiconductor substrate during a thermal diffusion step that is part of the integrated circuit fabrication technique, each of the plurality of island areas having the minimum geometry feature;"

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Stanetta D. Isaac whose telephone number is 571-272-1671. The examiner can normally be reached on Monday-Friday 9:30am -6:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Lebentritt can be reached on 571-272-1873. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Stanetta Isaac Patent Examiner December 5, 2006

MICHAEL LEBENTRITT SUPERVISORY PATENT EXAMINER